

FORM PTO-1449 (modified)  
To: U.S. Department of Commerce  
(PW FORM PAT-1449)  
Patent and Trademark Office

Atty.  
Dkt. No.

Client Ref.

281487

P-0198.020-US

**INFORMATION DISCLOSURE STATEMENT  
BY APPLICANT**

Applicant: BASELMANS et al.

Appln. No.: 09/905,198

Filing Date: July 16, 2001

Examiner: UNKNOWN

Group Art Unit: 2872

Date: December 31, 2002

Page

1

of

1

**U.S. PATENT DOCUMENTS**

Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
SPM	AR	6,074,787	06/2000	TAKEUCHI	TECHNOLOGY CENTER 2800	1	
	BR						
	CR						
	DR						
	ER						
	FR						
	GR						
	HR						
	IR						
	JR						
	KR						
	LR						
	MR						
	NR						

**FOREIGN PATENT DOCUMENTS**

		Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract	Translation Readily Available
	OR					Enclosed	No
	PR						
	QR						
	RR						
	SR						
	TR						
	UR						
	VR						
	WR						

**OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)**

SPM	XR	Kroyan et al., "Effects of Sub-Resolution Assist Features on Depth of Focus and Uniformity of Contact Windows for 193 nm Lithography," <i>Part of the SPIE Conference on Optical Microlithography XII</i> , Santa Clara, CA, March 1999, vol. 3679, pt. 1-2, pp. 630-638.			
	YR				
	ZR				
	AAR				

Examiner

Mohamedalla

Date Considered:

11/3/03

\*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.